PROCEEDINGS OF SPIE

Advanced Laser Processing and Manufacturing III

Rongshi Xiao Minghui Hong Jian Liu Jianhua Yao Yuji Sano Editors

21–22 October 2019 Hangzhou, China

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Published by SPIE

Volume 11183

Proceedings of SPIE 0277-786X, V. 11183

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Advanced Laser Processing and Manufacturing III, edited by Rongshi Xiao, Minghui Hong, Jian Liu, Jianhua Yao, Yuji Sano, Proc. of SPIE Vol. 11183, 1118301 · © 2019 SPIE CCC code: 0277-786X/19/\$21 · doi: 10.1117/12.2560388

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Please use the following format to cite material from these proceedings:

Author(s), "Title of Paper," in Advanced Laser Processing and Manufacturing III, edited by Rongshi Xiao, Minghui Hong, Jian Liu, Jianhua Yao, Yuji Sano, Proceedings of SPIE Vol. 11183 (SPIE, Bellingham, WA, 2019) Seven-digit Article CID Number.

ISSN: 0277-786X

ISSN: 1996-756X (electronic)

ISBN: 9781510630833

ISBN: 9781510630840 (electronic)

Published by

SPIE

P.O. Box 10, Bellingham, Washington 98227-0010 USA Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445 SPIE.org

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Contents

V	Authors
vii	Symposium Committees
xi	Conference Committee
	LASER MICRO/NANOFABRICATION AND ULTRAFAST LASER PROCESSING I
11183 05	Investigation on UV solid-state nanosecond laser micromachining of microstructures on sapphire wafer [11183-4]
	LASER MICRO/NANOFABRICATION AND ULTRAFAST LASER PROCESSING II
11183 07	Laser-induced backside wet/dry etching microstructures on transparent and brittle materials (Invited Paper) [11183-6]
11183 09	Laser-induced hierarchically-structured materials from block copolymer self-assembly [11183-10]
11183 0A	Fabrication and testing of the smallest "flute" on syringe needles [11183-9]
	LASER MACRO PROCESSING
11183 OB	Fabrication of high strength and lightweight dissimilar material joints by laser: a review (Invited Paper) [11183-11]
11183 OD	Numerical simulation of fiber laser cutting CFRP with different resin matrix contents [11183-13]
11183 OF	Research on the effect of microtexturing pretreatment on laser welding of CFRTP and aluminum alloy $[11183-15]$
	LASER ADDITIVE MANUFACTURING AND LASER PEENING I
11183 01	AlCrFeMnNi high-entropy alloy fabricated by laser additive manufacturing under direct-current electric field controlled [11183-18]

POSTER SESSION

11183 OR	Research on picosecond laser processing technology of ceramic materials involving incident angle [11183-8]
11183 OT	The anti-icing characteristics of micro/nano surface of stainless steel prepared by femtosecond laser [11183-28]
11183 OU	Fast formation of hybrid periodic surface structures on Hf thin-film by focused femtosecond laser beam [11183-29]
11183 OW	Laser and electrochemical hybrid machining (LECM) based on internal total reflection effect [11183-31]
11183 OX	Simulation and experimental verification of water-guided laser processing by a water-gas shrinkage laminar flow method [11183-32]
11183 OY	Effect of energy input on laser welded AlSi10Mg parts fabricates by selective laser melting [11183-33]

Authors

Numbers in the index correspond to the last two digits of the seven-digit citation identifier (CID) article numbering system used in Proceedings of SPIE. The first five digits reflect the volume number. Base 36 numbering is employed for the last two digits and indicates the order of articles within the volume. Numbers start with 00, 01, 02, 03, 04, 05, 06, 07, 08, 09, 0A, 0B...0Z, followed by 10-1Z, 20-2Z, etc.

Babin, S. A., OU Belousov, D. A., OU Bronnikov, K. A., OU Cao, Qing, 0Y Chang, Yaoqing, 0Y Chen, Xiaoxiao, OR Cui, Li, 0Y Dostovalov, A. V., 0U E., Yiwen, 0A Fan, A., 0D Gao, Shenghan, 0A Guo, Chunhai, 0X He, Dingyong, 0Y Huang, Hui, OY Jia, Shaohui, OF, OI Jiao, Junke, OF, OI Jin, Zeging, OA Korolkov, V. P., 0U Li, J. G., 07 Li, M. N., 07 Lin, Jingquan, OT Liu, Y., 05 Liu, Ziyuan, OT Long, J. Y., 07 Ouyang, Wentai, 0F, 01 Qi, L., 05, 0D Shen, Zhikang, OB Tan, Caiwang, OB Tan, Kwan W., 09 Tao, Haiyan, OT Wang, Heng, OR Wang, Yufeng, 0W Wu, Yaowen, 0X Xiao, Rui, OB Xie, X. Z., 07 Xu, Zifa, OF, OI Yang, Feng, 0W Yang, Jin, OB Ye, Yiyun, OF, OI Yu, Zhishui, OB Zeng, Yong, 0Y Zhang, Guangyi, 0X Zhana, Mina, OF, OI Zhang, Mingchi, OT Zhang, Wenwu, OF, OI, OR, OW, OX Zhang, X.-C., 0A Zhang, Zheng, 0X

Zhou, C. X., 07 Zou, Z. S., 07

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